

Cleaning method, cleaning apparatus and electro optical device

Publication number: TW278536B

Publication date: 2007-04-11

Inventor: HOSODA TOSHIKO (JP); YOTSUYA SHINICHI (JP)

Applicant: SEIKO EPSON CORP (JP)

Classification:

- International: *B08B3/08; C23F4/00; B08B3/00; B08B3/12; C23C14/00; C23C14/04; C23C14/24; H01L21/302; H01L21/44; H01L21/461; H01L51/50; H05B33/10; H05B33/14; B08B3/08; C23F4/00; B08B3/00; B08B3/12; C23C14/00; C23C14/04; C23C14/24; H01L21/02; H01L51/50; H05B33/10; H05B33/14;*

- European: *B08B3/12*

Application number: TW20040135877 20041122

Priority number(s): JP20030403071 20031202

Also published as:



US2005115594 (A)
JP2005161190 (A)
CN1623688 (A)

Report a data error he

Abstract of TW278536B

To provide a washing method and a washing apparatus capable of easily removing organic matter adhering to an evaporation mask of a low-molecular organic EL apparatus. The washing apparatus is an apparatus 1 for washing organic matter adhering to the evaporation mask of the low-molecular organic EL apparatus and comprises a first stage 10 for treating the evaporation mask 140 with a pyrrolidone derivative; a second stage 20 for rinsing the evaporation mask 140 with water; a third stage 30 for rinsing the evaporation mask 140 with flowing water; a fourth stage 40 for treating the evaporation mask 140 with ethanol; a fifth stage 50 for drying the evaporation mask 140; and transportation means 5 for successive transporting the evaporation mask 140 to the respective stages. It is preferable to use N-methyl-2-pyrrolidone as the pyrrolidone derivative.

Data supplied from the *esp@cenet* database - Worldwide